



Behind the Scenes of a European Infrastructure for micro and nano fabrication and characterisation

Karlsruhe Institute of Technology

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At Nanotechnology PL

Satellite event to E-MRS fall meeting

September 14th 2010

What is EUMINAfab?



- European Research Infrastructure for multimaterial micro and nano fabrication and characterisation
- 10 partners from 8 countries
- EC funded, FP7 Capacities, Total budget: 7.8 M€
- March 2009 – February 2013



What does EUMINAfab do?



- ★ Open innovation:

Offer no fee access to over 70 micro and nano-technologies

- ★ Knowledge management:

Technology capability mapping and technology readiness levelling

- ★ Technology integration:

Develop process chains and technology demonstrators

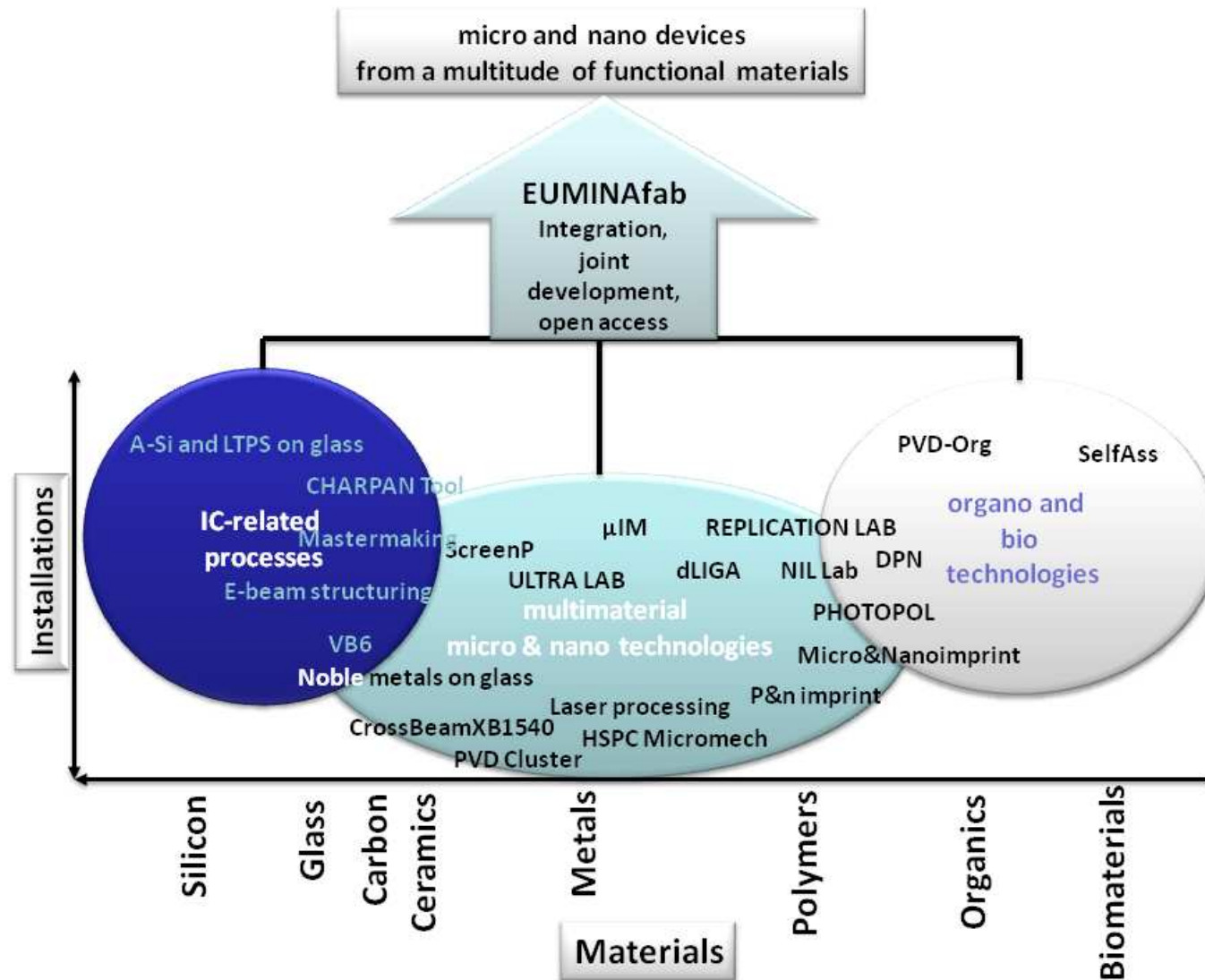
- ★ Increase mobility of scientists:

Summer/winter schools and researchers exchange programme

- ★ Build a sustainable infrastructure for micro and nano fabrication and characterisation

Further details on everything www.euminafab.eu
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Comprehensive process portfolio



36 installations → a MNT toolbox



μ and nanostructuring

- ✦ Electron beam
- ✦ E-beam & SCIL
- ✦ Ion beam (Focused cross beam)
- ✦ Ion beam (parallel ion beams)
- ✦ DPN
- ✦ Direct X-ray litho
- ✦ Laser technologies (e.g. ps, fs, surface texturation)
- ✦ Mechanical μmachining (freeform)
- ✦ Photopolymeristn.
- ✦ Mastermaking process chain
- ✦ DRIE (Si, glass, SiO₂)

Thin film deposition

- ✦ PVD technologies (e.g. noble metals, DLC, nanocomposites, metals, nitrides)
- ✦ Org. PVD (e.g. organic liquids & powders, oxides)
- ✦ CVD (metals, polymers, ceramics)
- ✦ Self Assembly (e.g. semiconductors, organic)
- ✦ Screen printing (e.g. metals, dielectrics)
- ✦ Optical Coating

Replication

- ✦ μ injection moulding (e.g. polymers, metals, ceramics; small series)
- ✦ μ hot embossing (small series)
- ✦ Thermal imprinting & UV-NIL
- ✦ NIL process chain (UV photolitho, dry & wet etching)

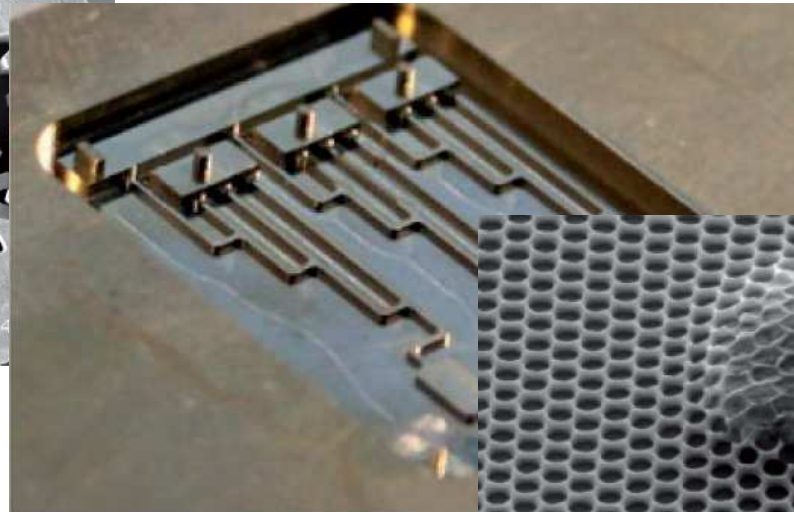
Characterisation

- ✦ HRTEM
- ✦ XPEEM
- ✦ Auger Nanoprobe
- ✦ In situ synchrotron X-ray diffractometry (> 2010)
- ✦ AFM, conductive AFM
- ✦ Spectrophotometry /-radiometry
- ✦ Profilometry (e.g. low force contact mode & white light mode)
- ✦ μCMM
- ✦ Low force balance, ellipsometry

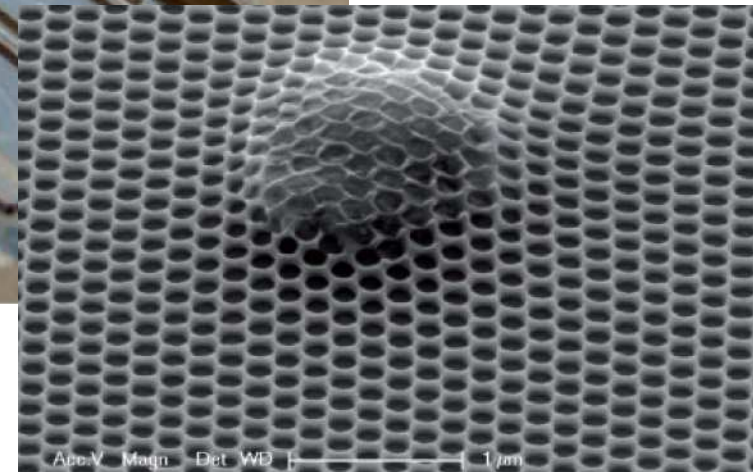
Some Examples Micro – Nano Patterning



**mechanical
microstructures**
(© TEKNIKER)



mould inserts
(© Cardiff University)



**nano printing on curved
surfaces**
(© Philips MiPlaza)

Some Examples: Thin film deposition



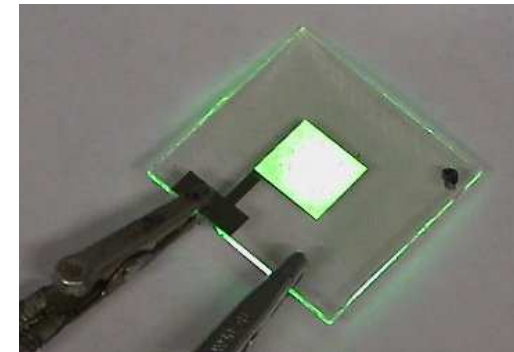
★CVD

★PVD Cluster for layers and coating tools and organic device fabrication

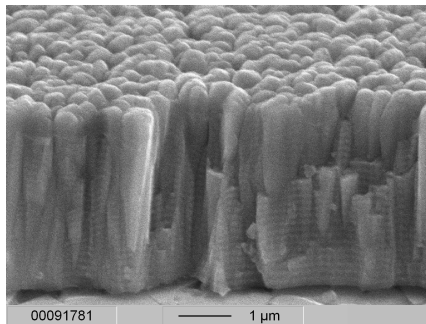
★Self assembling tools

★Thin film noble metals

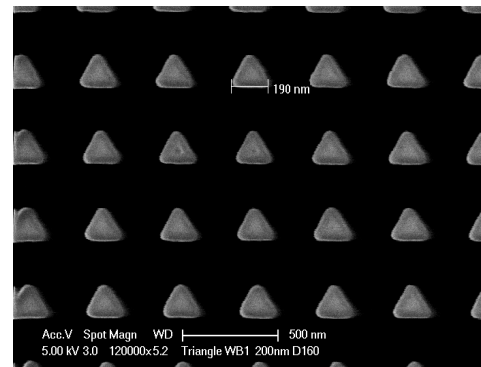
★Optical Coatings: new September 2010



OLED single pixel (10x10 mm) fabricated by vacuum deposition
© Centro Ricerche FIAT



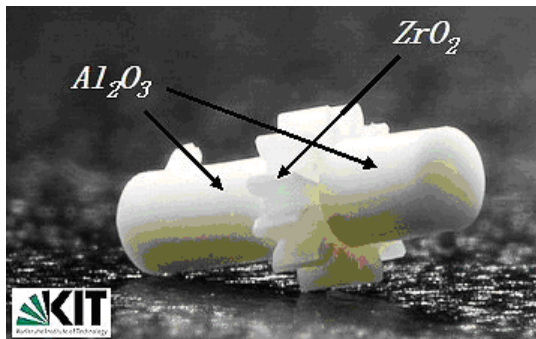
Fracture surface of a TiN/ZrN multilayer coating © KIT



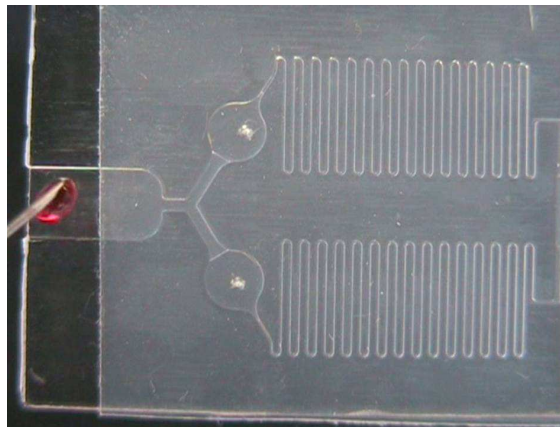
Noble metals Thin film deposition: 10-1000 nm
© MiPlaza

Some Examples: Replication

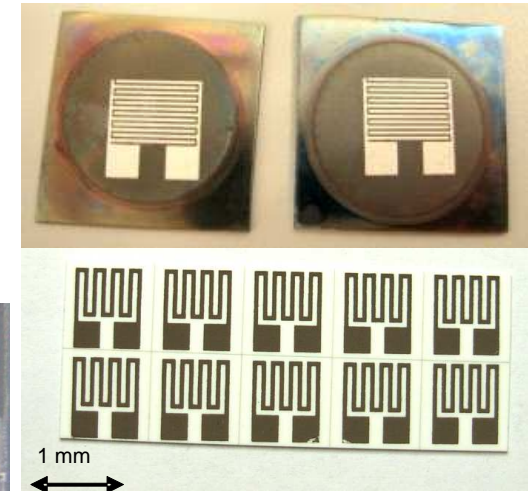
- ★ Micro & Nano Imprinting
- ★ Micro injection moulding
- ★ Reactive ion etching
- ★ Hot embossing



Combined gear wheel / shaft
2C injection moulding © FZK



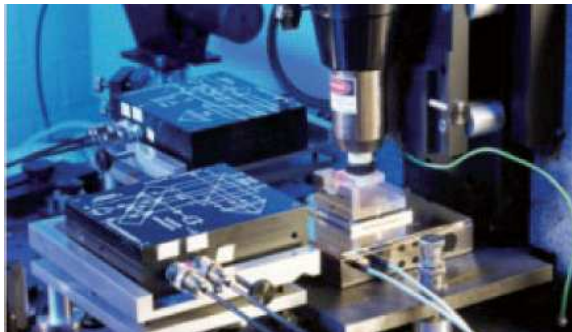
Microfluidic device replicated by hot
embossing in a 1 mm thick PMMA film
(© TEKNIKER)



Screen printed Ni on
alumina and Ag on porous
titania for **gas sensors** (©
Centro Ricerche FIAT)

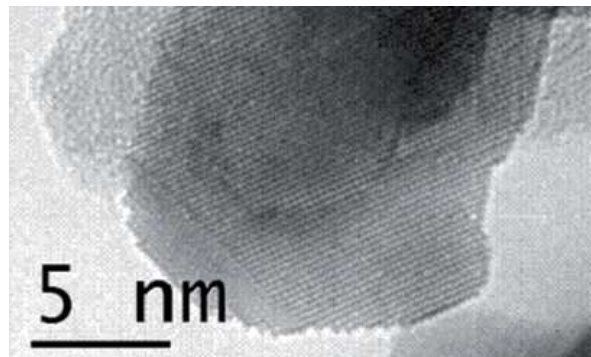
Some Examples: Characterisation

- ★ Transmission Electron Microscopy
- ★ NANO Beam Line (from 2010)
- ★ Electro-optical characterization
- ★ Metrology

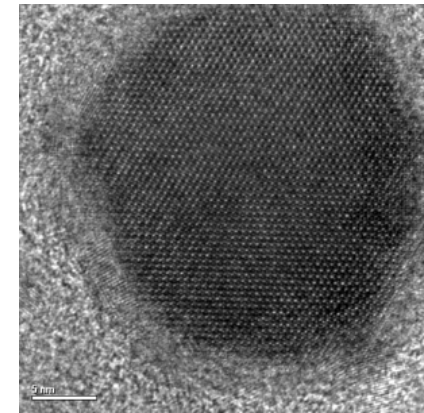


**metrological atomic
force microscopy**

© NPL



**nanomaterials
characterisation**
© CEA Grenoble



HRTEM image of
Co/CoO particles
showing the **atomic
arrangement** ©
Forschungszentrum
Karlsruhe/KNMF

....in the area of micro nano fabrication and characterisation

....do you have all **necessary capacities & capabilities** to realize your ideas



User request form

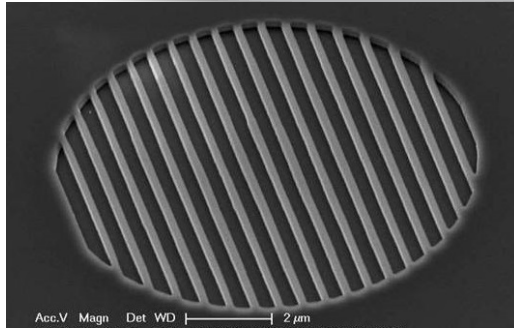
- ★ Project summary
 - Work to be performed
 - Reasons for selecting each technology
 - Critical dimensions

- ★ Technology portfolio
 - Select technologies
 - Level of experience

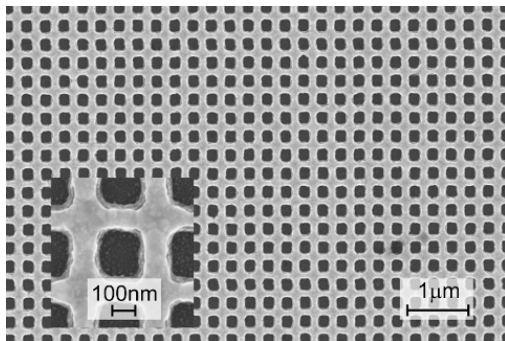
www.euminafab.eu

Project Summary	
Should include work to be performed, reasons for selecting each technology, critical dimensions to be reached.	
Project identifier	Technologies (optional) Select one or more technologies which you prefer.
Describe your project	Micro and nano patterning technologies: <ul style="list-style-type: none"><input type="checkbox"/> CHARPAN - Charged Particle Nanopatterning<input type="checkbox"/> Dip-Pen Nanolithography<input type="checkbox"/> Direct X-Ray Lithography<input type="checkbox"/> E-Beam and SCIL<input type="checkbox"/> Electron Beam Lithography<input type="checkbox"/> FIB/SEM Cross Beam XB1540<input type="checkbox"/> HSPC micromachine (Diamond Milling)<input type="checkbox"/> Laser Material Processing @ Cardiff<input type="checkbox"/> Laser Material Processing @ Karlsruhe<input type="checkbox"/> Mastermaking<input type="checkbox"/> NIL LAB - Modules for Micro and Nanoreplication<input type="checkbox"/> Photopolymer technology<input type="checkbox"/> Surface nanotexturation<input type="checkbox"/> ULTRA LAB - Ultraprecision machining
	Thin film deposition technologies: <ul style="list-style-type: none"><input type="checkbox"/> FB-MOCVD<input type="checkbox"/> LTPS Line<input type="checkbox"/> Noble Metal<input type="checkbox"/> PVD Magnetron<input type="checkbox"/> PVD Cluster for metals, ceramic and glass<input type="checkbox"/> PVD-Cluster for organic device fabrication<input type="checkbox"/> DLI - MOCVD<input type="checkbox"/> Self Assembly tools
	Replication technologies: <ul style="list-style-type: none"><input type="checkbox"/> Etching: DRIE and RIE<input type="checkbox"/> Polymer and nanoimprinting<input type="checkbox"/> Micro-Injection Moulding<input type="checkbox"/> Micro and Nano Imprinting<input type="checkbox"/> REPLICATION LAB - Microreplication<input type="checkbox"/> Screen printing machine
	Characterisation technologies: <ul style="list-style-type: none"><input type="checkbox"/> Auger nanoprobe<input type="checkbox"/> Electro-optical characterization<input type="checkbox"/> HRTEM TITAN<input type="checkbox"/> METRO LAB - Micrometrology<input type="checkbox"/> Metrology at NPL<input type="checkbox"/> TEM<input type="checkbox"/> XPEEM

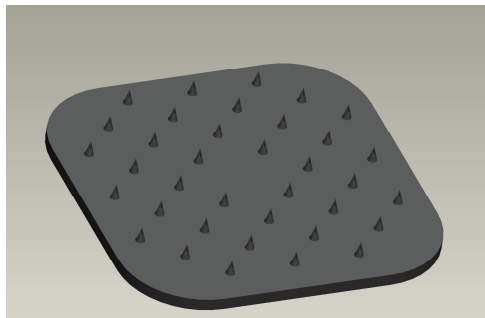
Focus technological applications three presentations



Nanofabrication - direct write and
replication patterning technologies in
EUMINAfab
Frank Dirne Miplaza Philips Research



Micro and nanofabrication technologies
for optical and sensor applications
Jorge Ramiro TEKNIKER



Mastermaking and Structuring Facilities
Steffen Scholz Cardiff University



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- ✳ Funding by the European Community, funded under the FP7 specific programme Capacities
- ✳ E-MRS and Nanotechnology PL for the opportunity and kind assistance in staging this workshop



Some of the people behind the scenes



**Your gateway to multimaterial
micro nano fabrication**

www.euminafab.eu